

**PATENT**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicants:	Ishiduka, et al.	Examiner:	Johnson, Connie P.
Application No.:	10/591,718	Group Art Unit:	1722
Confirmation No:	3280	Docket:	1608-7 PCT/US/RCE III
Filed:	September 5, 2006	Dated:	April 27, 2012
For:	POSITIVE-TYPE RESIST COMPOSITION FOR LIQUID IMMERSION LITHOGRAPHY AND METHOD FOR FORMING RESIST PATTERN		

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

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I hereby certify that this correspondence is being transmitted to the U.S. Patent and Trademark Office via the Office's electronic filing system.

Dated: April 27, 2012

Signature: Marcy Mancuso /Marcy Mancuso/

**AMENDMENT AND RESPONSE ACCOMPANYING**  
**A REQUEST FOR CONTINUED EXAMINATION**

Sir:

This submission is in response to the final Office Action mailed on October 28, 2011, the due date for which is April 28, 2012, with a three-month extension of time. A Request for Continued Examination is being filed concurrently herewith. Entry of the amendments and reconsideration are respectfully requested.

**Amendments to the Claims** begin on page 2 of this submission.

**Remarks** begin on page 7 of this submission.